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Properties of transparent oxide thin films prepared by plasma deposition

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Abstract

In this paper, thin films of TiO_2 were deposited onto (100) oriented silicon and glass substrates using low pressure hot target reactive magnetron sputtering (LP HTRS) method. X-ray diffraction (XRD) and optical transmission measurements have been applied to study the influence of substrate type on the microstructure and optical properties of the prepared thin films, respectively. Thin films exhibit the TiO_2 -anatase crystalline state, which could be confirmed by the appearance of peaks of (101) orientation.



45.3 kB

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